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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/735,374	12/12/2003	Betty Shu Mercer	TI-36853	1822

23494 7590 04/20/2007  
TEXAS INSTRUMENTS INCORPORATED  
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EXAMINER
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ANDUJAR, LEONARDO

ART UNIT	PAPER NUMBER
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2826

SHORTENED STATUTORY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE
3 MONTHS	04/20/2007	PAPER

**Please find below and/or attached an Office communication concerning this application or proceeding.**

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

<b>Office Action Summary</b>	<b>Application No.</b>	<b>Applicant(s)</b>	
	10/735,374	MERCER ET AL.	
	<b>Examiner</b>	<b>Art Unit</b>	
	Leonardo Andújar	2826	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

#### Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

#### Status

- 1) ☒ Responsive to communication(s) filed on 10 January 2007.
- 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

#### Disposition of Claims

- 4) ☒ Claim(s) 1-3, 7, 16, 17, 19-23 and 33-36 is/are pending in the application.
- 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.
- 5) ☐ Claim(s) \_\_\_\_\_ is/are allowed.
- 6) ☒ Claim(s) 1-3, 7, 16, 17, 19-23 and 33-36 is/are rejected.
- 7) ☐ Claim(s) \_\_\_\_\_ is/are objected to.
- 8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

#### Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on \_\_\_\_\_ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.  
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

#### Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some \* c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

#### Attachment(s)

- |   |   |
|---|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)             | 4) <input type="checkbox"/> Interview Summary (PTO-413)                     |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)    | Paper No(s)/Mail Date: _____  |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| Paper No(s)/Mail Date: _____  | 6) <input type="checkbox"/> Other: _____                                    |

## DETAILED ACTION

### *Acknowledgment*

1. The amendment filed on 01/10/2007 in response to the Office action mailed on 09/05/2006 has been entered. The present Office action is made with all the suggested amendments being fully considered. Accordingly, pending in this Office action are claims 1-3, 7, 16, 17, 19-23 and 33-36.

### *Election/Restrictions*

2. Applicant's election without traverse of claims 1-3, 7, 16, 17 and 19-23 in the reply filed on 06/27/2006 is acknowledged.

### *Claim Rejections - 35 USC § 103*

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

4. Claims 1-3, 7, 33 and 34 rejected under 35 U.S.C. 103(a) as being unpatentable over Jeong (US 6,545,358) in view of Thomas et al. (US 5,117,276).

5. Regarding claim 1, Jeong (e.g. 3) shows an integrated circuit, comprising: a semiconductor substrate 21 comprising device elements and one or more metallization layers interconnecting the device elements and having an uppermost layer 23 comprising metal regions; a protective overcoat 27 formed over the metallization layers, the protective overcoat having vias 37 through it; tungsten plugs 41 substantially filling the vias and connecting to one of the metal regions in the uppermost layer; and thick copper 45 formed over the protective overcoat and forming connections to the tungsten plugs (clm. 1 and 18). Although it is well

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known in the art that the uppermost layer (i.e. Jeong's 23) include multiple metal regions disposed between dielectric regions Jeong does not explicitly show it. However, Thomas (e.g. fig. 1K) shows an uppermost layer comprised by metal regions 108 disposed between dielectric regions (14, 15 & 30). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the uppermost layer disclosed by Jeong having multiple metal regions disposed between dielectric regions as suggested by Thomas to interconnect the plurality of electrical device formed on the semiconductor device.

6. Regarding claim 2, Jeong teaches that the uppermost layer is an aluminum metallization (col.3/lis. 9-10).

7. Regarding claims 3, Jeong teaches that the protective overcoat is made of silicon oxide (col. 4/lis. 60).

8. Regarding claims 7, Jeong teaches that the thick copper forms interconnections between device elements within the integrated circuit (col. 1/lis. 55-62).

9. Regarding claim 33, Jeong in view of Thomas show that the metal plugs couple at least one of the thick copper connections to one of the metal regions.

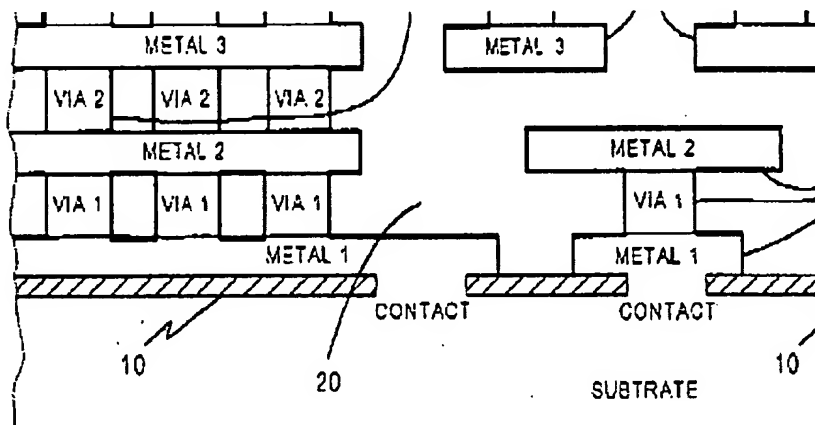
10. Regarding claim 34, Jeong in view of Thomas shows that the thick copper substantially overlies at least one of the metal regions.

11. Claims 16, 19-23 and 36 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jeong (US 6,545,358) in view of Buynoski (US 6,218,282).

12. Regarding claims 16 and 20, Jeong (e.g. fig. 3) shows an integrated circuit, comprising: a semiconductor substrate 21 comprising device elements and one or more metallization layers interconnecting the device elements and having an uppermost layer 23 comprising pads; a protective overcoat 27 formed over the metallization layers, the protective overcoat having vias 37 through it; wherein the array of vias are formed over individual bond pads, tungsten plugs 41

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substantially filling the vias and connecting to the uppermost layer bond pads; and thick copper 45 formed over the protective overcoat and forming connections to the tungsten plugs (clm. 1 and 18). Jeong does not teach that multiple vias are formed over individual bond pad. Nonetheless, Buynoski (e.g. fig. 4) shows an integrated circuit having multiple vias 1 formed over individual bond pads (metal 1).



It would have been obvious to one having ordinary skill in the art at the time the invention was made to form multiple vias over individual bond pads disclosed by Jeong as suggested by Buynoski to increase device density and performance.

Regarding claim 19, Jeong teaches that the plug is made of tungsten with have a coefficient of thermal expansion less than or equal to about 8 ppm/C.

13. Regarding claim 21, Jeong teaches that the uppermost layer is an aluminum metallization (col.3/lis. 9-10).

14. Regarding claim 22, Jeong teaches that the protective overcoat is made of silicon oxide (col. 4/lis. 60).

15. Regarding claim 23, Jeong teaches that the thick copper forms interconnections between device elements within the integrated circuit (col. 1/lis. 55-62).

16. Regarding claim 36, Jeong in view of Buynoski shows that the multiple metal plugs individually couple the thick copper connection to the bond pads.

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17. Claim 17 rejected under 35 U.S.C. 103(a) as being unpatentable over Jeong (US 6,545,358) in view of Buynoski (US 6,218,282) further in view of Ting et al. (US 5,969,422).

18. Regarding claim 17, Jeong in view of Buynoski discloses the claimed invention except for a plug made of copper. Ting teaches that copper is a suitable material for contact plugs (abstract, col. 6/lls. 10-15)). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the contact plug disclosed by Jeon in view of Buynoski of copper as suggested by Ting, since it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use as a matter of obvious design choice. *In re Leshin*, 125 USPQ 416.

19. Claim 35 is rejected under 35 U.S.C. 103(a) as being unpatentable over Jeong (US 6,545,358) in view of Thomas et al. (US 5,117,276) further in view of Or-Bach et al. (US 6,476,493).

20. Regarding claim 35, Jeong in view of Thomas teaches most aspects of the instant invention including a thick copper but does not explicitly teaches that the thick copper layer does not extend over at least a portion of the dielectric region. However, it is implicitly disclosed because metal interconnections are arranged as grid type array. Therefore, it is not possible for a layer to overlay the whole surface of the integrated circuit unless the layer is a metal plane. For example Or-Bach (e.g. fig. 3) shows the different interconnection metal levels interconnected by vias wherein an upper layer does not extend over the dielectric regions of a lower level (i.e. the space defined by at least two metal layers in the same level). It would have been obvious to one having ordinary skill in the art at the time the invention was made to make the thick copper layer such as to do not extend over at least a portion of the dielectric region disclosed by Jeong in view of Thomas to provide an interconnection system which has minimal parasitic capacitance and it is mechanically strong.

***Response to Arguments***

21. Applicant's arguments filed on 01/10/2007 have been considered but are moot in view of the new ground(s) of rejection.

***Conclusion***

22. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a). A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.


23. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Leonardo Andújar whose telephone number is 571-272-1912. The examiner can normally be reached on Mon through Thu from 9:00 AM to 7:30 PM EST.

24. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Sue Purvis can be reached on 571-272-1236. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

25. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR

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system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.



Leonardo Andujar  
Primary Examiner  
Art Unit 2826

04/14/2007